

Silylene Complexes from a Stable Silylene and Metal Carbonyls: Synthesis and Structure of $[\text{Ni}\{\text{(Bu}^t\text{N-CH=CH-NBu}^t\text{)Si}\}_2(\text{CO})_2]$, a Donor-free Bis-silylene Complex

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$[\text{Ni}(\text{LSi})_2(\text{CO})_2]$ **3**; the first silylene complex of nickel, has been obtained from the stable silylene 1,3-di-*tert*-2,3-dihydro-1*H*-1,3,2-diazasilol-2-ylidene (LSi) **1** and tetracarbonylnickel; complex **3** was characterized by single crystal X-ray diffraction and NMR spectroscopy (^1H , ^{13}C , ^{29}Si).

Silylenes, like carbenes, have been shown to form stable metal complexes.¹⁻³ Unlike the carbene complexes, silylene complexes usually require additional stabilization by a Lewis base coordinated to silicon. The structure of the first base-free silylene complex has only recently been reported.³

The synthesis of 1,3-di-*tert*-butyl-2,3-dihydro-1*H*-1,3,2-diazasilol-2-ylidene **1**,⁴ a stable silylene,⁵ provided the possibility to obtain silylene complexes by CO substitution from metal carbonyls. Reaction of **1** with $\text{Ni}(\text{CO})_4$ gave the bis-silylene complex **3** in nearly quantitative yield.[†] Compound **3** is the first silylene complex of nickel as well as the first bis-silylene complex without Lewis base stabilization. It is highly air- and moisture-sensitive but quite stable thermally (mp 160 °C, decomp.). No monosubstitution product **2** was observed on changing the reaction conditions [inverse addition of **1** to a large excess of $\text{Ni}(\text{CO})_4$ at -80 °C] or on the attempted comproportionation of **3** with $\text{Ni}(\text{CO})_4$ ⁷ (Scheme 1).

The structure of **3**, determined by single crystal X-ray diffraction,[‡] shows a slightly distorted tetrahedral arrange-

ment of two silylene and two carbonyl ligands around nickel. The $\text{C}_2\text{N}_2\text{Si}$ units of both silylene ligands are planar. The coordination geometry of nickel in **3** is similar to that of the CC saturated germanium analogue.⁶

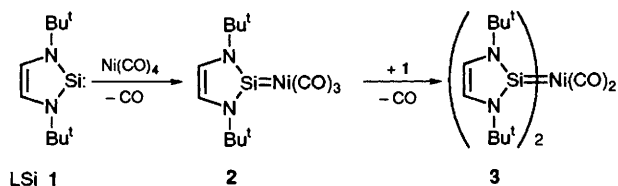
The N-Si-N angle of **3** is remarkably small (90°), its value being close to what was predicted⁷ for free silylenes. The Si-Ni bond is short; bond lengths reported for silylene complexes of iron, chromium and manganese¹ are typically 10–15 pm longer than the Si-Ni bond in **3**. A recent theoretical study predicts a Si-Ni bond length of 229 pm.⁸

The CO stretching frequencies and the chemical shift, $\delta(^{13}\text{C})$, of the carbonyl groups of **3** are both nearly identical with the values reported for the phosphine complex $[\text{Ni}(\text{Ph}_3\text{P})_2(\text{CO})_2]$ [ν/cm^{-1} ,⁹ 2000 (A_1) and 1941 (B_1); $\delta(^{13}\text{C})$,¹⁰ 199.4].

Silicon NMR studies show the silicon nucleus to experience moderate deshielding upon coordination (**1** + 78.4 ppm, **3** + 97.5 ppm);§ all other NMR shifts show little change. No satellites due to coupling to ^{61}Ni could be detected.

This work was supported by a grant to M. D. from the Alexander von Humboldt Foundation.

Received, 20th May 1993; Com. 3/02901H



Scheme 1

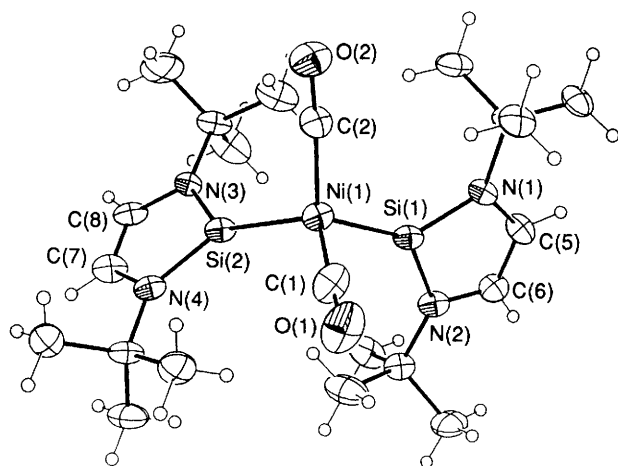


Fig. 1 Molecular structure of $[\text{Ni}\{\text{Bu}^t\text{-NCH=CHN-Bu}^t\text{)Si}\}_2(\text{CO})_2]$ **3**. ORTEP view with hydrogen atoms omitted for clarity. Thermal ellipsoids are at the 50% probability level. Selected bond distances (pm) and bond angles (°) as follows: Ni(1)-Si(1) 220.7(2), Ni(1)-Si(2) 221.6(2), Ni(1)-C(1) 177.8(7), Ni(1)-C(2) 176.1(6), C(1)-O(1) 113.9(9), C(2)-O(2) 115.7(7), Si(1)-N(1) 174.5(5), Si(1)-N(2) 174.3(5), Si(2)-N(3) 174.9(5), Si(2)-N(4) 174.5(5), N(1)-C(5) 138.6(7), N(2)-C(6) 140.2(9), N(3)-C(8) 139.7(8), N(4)-C(7) 139.3(9), C(5)-C(6) 134.4(8), C(7)-C(8) 133.0(9), Si(1)-Ni(1)-Si(2) 108.4(1), Si(1)-Ni(1)-C(1) 103.5(2), Si(1)-Ni(1)-C(2) 112.5(2), Si(2)-Ni(1)-C(1) 115.3(3), Si(2)-Ni(1)-C(2) 106.2(2), C(1)-Ni(1)-C(2) 111.1(3), N(1)-Si(1)-N(2) 90.0(2), N(3)-Si(2)-N(4) 89.9(2).

Footnotes

[†] Synthesis of **3**: compound **1** (0.158 ml, 1.22 mmol) was added to a solution of $\text{Ni}(\text{CO})_4$ (480 mg, 2.44 mmol) in *n*-hexane (5 ml) at room temperature. After CO evolution ceased (ca. 5 min) stirring was continued for 1 h. Cooling to +5 °C (2 h) then -25 °C (1 day) gave 576 mg (93%) of **3** after filtration and drying.

[‡] Crystal data for **3**: $\text{C}_{22}\text{H}_{40}\text{N}_4\text{NiSi}_2\text{O}_2$, $M = 507.5$, crystal size = $0.1 \times 0.2 \times 0.2$ mm, monoclinic, space group $P2_1/c$, $a = 9.4873(15)$, $b = 16.374(2)$, $c = 17.8784(15)$ Å, $\beta = 105.245(11)^\circ$, $V = 2679.5(5)$ Å³, $Z = 4$, $D_c = 1.258$ g cm⁻³, $\lambda(\text{Cu-K}\alpha) = 1.54178$ Å, $\mu(\text{Cu-K}\alpha) = 2.087$ mm⁻¹, $F(000) = 1088$, scan type $2\theta-\theta$, $T = 113(2)$ K, $4.0 < 2\theta < 114.0^\circ$, total unique data 3571 ($R_{\text{int}} = 10.6\%$), no. of observations [$(F) > 4\sigma(F)$] 2745, observations/variables 9.7, $R = 0.068$, $R_w = 0.089$, maximum peak in final Fourier difference synthesis 1.13 e Å⁻³. Data were collected on a Siemens P4 diffractometer. No absorption correction was applied. Lorentz and polarisation corrections were applied. Systematically absent reflexions were rejected and equivalent reflexions were merged. The heavy-atom positions were determined by direct methods. Subsequent difference Fourier synthesis revealed the positions of all other non-hydrogen atoms; organic hydrogen atoms were put into idealized position. The non-hydrogen atoms were refined by the full-matrix least-squares method with the hydrogen atoms 'riding' on their supporting carbon atoms. A weighting scheme [$w^{-1} = \sigma^2(F) + 0.001F^2$] was applied and the data were corrected for the effects of anomalous dispersion and secondary extinction. Crystallographic calculations were carried out using the Siemens SHELXTL PLUS program¹¹ on a Silicon Graphics Indigo system.

Atomic coordinates, bond lengths and angles, and thermal parameters have been deposited at the Cambridge Crystallographic Data Centre. See Notice to Authors, Issue No. 1.

§ NMR data were recorded at room temperature in C_6D_6 solution at 200 MHz (^1H), 126 MHz (^{13}C) and 99.3 MHz (^{29}Si). Selected spectroscopic data for **1**: ^1H NMR δ 1.40 (18 H, s, CMe_3) and 6.74 (2 H, s); ^{13}C NMR δ 30.3 (1J 125.7 Hz, CMe_3), 54.0 (CMe_3) and 120.0 (dd, 1J 176.1 Hz, 2J 11.0 Hz, =CH); ^{29}Si NMR δ +78.4 (s).

For **3**: $^1\text{H NMR}$: δ 1.46 (18 H, s, CMe_3) and 6.57 (2 H, s); $^{13}\text{C NMR}$ δ 33.3 (1J 125.7 Hz, CMe_3), 55.2 (CMe_3), 119.1 (dd, 1J 179.5 Hz, 2J 9.0 Hz, =CH) and 201.0 (CO); $^{29}\text{Si NMR}$ δ +97.5 (s); IR (CsBr, Nujol) ν/cm^{-1} 2011w, 2001s, 1995m, 1983w, 1945s, 1366s, 1260s, 1212m, 1144w, 1096mbr, 1022sbr, 806s, 729m, 671m, 510w and 461 w.

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